Session Title:	[TF2] Frontier Metrology and Modeling IV
Session Date:	November 21 (Tue.), 2023
Session Time:	10:20-11:50
Session Room:	Room F (Sicily Room, 1F)
Session Chair:	Dr. Byoung-Ho Lee (Hitachi Hightech, Korea)

[TF2-1] [Invited] 10:20-10:50

Methodology for Efficient Inspection of Wafer Defects in Very Low Volume Manufacturing (VLVM)

Tae Yong Lee (imec, Belgium)

[TF2-2] [Invited] 10:50-11:10

Analysis Theory and Method of Single Particle ICP-MS

Jae-Hong Park (Agilent Technologies, Korea)

[TF2-3] 11:10-11:30

Characterization of Nanoparticles in Size and Particle Concentration by Inductively Coupled Plasma-Mass Spectrometry

H. B. Lim (Ram Tech., Korea), Sukman Jang (DuPont Korea, Korea), Minseo Song (Dankook Univ., Korea), and Youngsu Jang (Ram Tech., Korea)

[TF2-4] 11:30-11:50

Uniformity Monitoring of Photoresist Etching Using Multi-Channel Optical Emission Spectroscopy

Sanghee Han, Sang Hun Lee (Sungkyunkwan Univ., Korea), Im Su Yoo (WGS Co., Ltd., Korea), and Heeyeop Chae (Sungkyunkwan Univ., Korea)